

L Number	Hits	Search Text	DB	Time stamp
-	1707	((remov\$3 strip\$4) with photoresist) same ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") and (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/21 14:55
-	504	((remov\$3 strip\$4) with photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") and (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/15 23:58
-	111	((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near3 (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/15 23:58
-	88	((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near2 (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/16 00:09
-	9	((remov\$3 strip\$4) adj photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/15 23:58

-	15	((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/16 00:10
-	6	((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH")) not ((remov\$3 strip\$4) adj photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/16 00:10
-	73	((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near2 (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH")) not ((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/16 00:26

-	23	((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near3 (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH")) not (((remov\$3 strip\$4) near photoresist) with ((reducing H2 NH3 "H.sub.2" "NH.sub.3" CnH2n+2 CnH2n "C.sub.n H.sub.2n+2" "C.sub.n H.sub.2n" CH4 C2H6 CH32CHCH3 "CH.sub.4" "C.sub.2 H.sub.6" "(CH.sub.3 ).sub.2 CHCH.sub.3" alkane methane ethane isobutane alkene ethene ethylene propene propylene C2H4 C3H6 "C.sub.2 H.sub.4" "C.sub.3 H.sub.6") near2 (oxidizing oxidation oxygen water carbon adj (monoxide dioxide) O2 H2O CO CO2 "O2.sub." "H.sub.2 O" "CO.sub.2" ROH alcohol EtOH ethanol C2H5OH "C.sub.2 H.sub.5 OH"))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/16 00:26
-	9	rf with bias with baffle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/21 14:58
-	10	rf same bias\$3 with baffle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/21 15:00
-	1	(rf same bias\$3 with baffle) not (rf with bias with baffle)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/21 14:59
-	34	rf same bias\$3 same baffle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/21 15:00
-	24	(rf same bias\$3 same baffle) not (rf same bias\$3 with baffle)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/21 15:00
-	1	((rf same bias\$3 same baffle) not (rf same bias\$3 with baffle)) and quartz near baffle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/21 15:01
-	9	(US-6562700-\$ or US-6503840-\$ or US-6534921-\$ or US-6352938-\$ or US-6178660-\$ or US-6031239-\$).did. or (US-20020111041-\$ or US-20020185151-\$).did. or (TW-442916-\$).did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/09 01:23
-	7	((US-6562700-\$ or US-6503840-\$ or US-6534921-\$ or US-6352938-\$ or US-6178660-\$ or US-6031239-\$).did. or (US-20020111041-\$ or US-20020185151-\$).did. or (TW-442916-\$).did.) and (wet solvent strip\$4 disolv\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 02:21
-	6369	(strip\$3 ash\$3 remov\$3 etch\$3) with (resist photoresist) same (deposit\$4 near (conduct\$3 metal\$3 copper aluminum))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 02:02

-	2	(strip\$3 ash\$3 remov\$3 etch\$3) with (resist photoresist) same (deposit\$4 near (conduct\$3 metal\$3 copper aluminum)) same (without near (solvent wet liquid rins\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 02:09
-	1	(strip\$3 ash\$3 remov\$3 etch\$3) with (resist photoresist) same (deposit\$4 near (conduct\$3 metal\$3 copper aluminum)) same (complet\$3 all) near dry	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 02:07
-	71	(strip\$3 ash\$3 remov\$3 etch\$3) with (resist photoresist) same (without near (solvent wet liquid rins\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 02:08
-	16	(strip\$3 ash\$3 remov\$3 etch\$3) with (resist photoresist) same (without near (solvent wet liquid rins\$3)) and (deposit\$4 near (conduct\$3 metal\$3 copper aluminum))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 02:09
-	2	((US-6562700-\$ or US-6503840-\$ or US-6534921-\$ or US-6352938-\$ or US-6178660-\$ or US-6031239-\$).did. or (US-20020111041-\$ or US-20020185151-\$).did. or (TW-442916-\$).did.) and baffle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 02:21